

**Notice of References Cited**

Application/Control No.

09/866,843

Applicant(s)/Patent Under  
Reexamination  
OGURE ET AL.

Examiner

George A. Goudreau

Art Unit

1763

Page 1 of 1

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
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	V	"Neutral-Beam-Assisted Etching of Silicon Dioxide-a Charge Free Etching Process"; □□Japanese Journal of Applied Physics; Part 1: Regular Papers, Short Notes & Review Papers (1990'); 29(10); Mizutani et. al.; abstract only
	W	
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
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